

Claims

- [c1] A method of controlling the concentration of a component in a composition, comprising:
providing a composition comprising a liquid portion, wherein the liquid portion comprises a component to be monitored;
performing an absorption spectroscopy measurement on a sample of the composition; and
controlling the concentration of the component in the composition based on the absorption spectroscopy measurement using a feedback control loop.
- [c2] The method according to claim 1, wherein the composition is a slurry used in a chemical mechanical planarization process or a solution used in a treatment bath prior to or after a chemical mechanical planarization process, in a semiconductor manufacturing process.
- [c3] The method according to claim 2, wherein the composition is a solution used in a treatment bath prior to or after a chemical mechanical planarization process, in a semiconductor manufacturing process.
- [c4] The method according to claim 2, wherein the component to be monitored is a corrosion inhibitor.
- [c5] The method according to claim 4, wherein the corrosion inhibitor is benzotriazole, tolyltriazole, imidazole, triazole, benzothiazole, mercaptobenzotriazole, hydroquinone, gallic acid, pyragallol, catechol, recorsinol, or a combination thereof.
- [c6] The method according to claim 2, wherein the composition is used in treating a substrate comprising a copper or copper-containing layer.
- [c7] The method according to claim 1, wherein the concentration of the component in the composition is controlled by adjustment of the amount of the component added to the composition.
- [c8] The method according to claim 1, wherein the concentration of the component in the composition is controlled by adjustment of the amount of a diluent added

to the composition.

- [c9] The method according to claim 1, wherein the absorption spectroscopy measurement is a UV/visible light spectroscopy measurement.
- [c10] The method according to claim 1, further comprising transporting the sample of the composition using a pump.
- [c11] A semiconductor processing method, comprising:
contacting a semiconductor wafer with a solution comprising a component to be monitored;
controlling the concentration of the component by a method comprising:
performing an absorption spectroscopy measurement on a sample of the solution; and
controlling the concentration of the component in the solution based on the absorption spectroscopy measurement using a feedback control loop.
- [c12] The method according to claim 11, wherein the component to be monitored is a corrosion inhibitor.
- [c13] The method according to claim 12, wherein the corrosion inhibitor is benzotriazole, tolyltriazole, imidazole, triazole, benzothiazole, mercaptobenzotriazole, hydroquinone, gallic acid, pyragallol, catechol, recorsinol, or a combination thereof.
- [c14] The method according to claim 11, wherein the concentration of the component in the solution is controlled by adjustment of the amount of the component introduced into the solution.
- [c15] The method according to claim 11, wherein the concentration of the component in the solution is controlled by adjustment of the amount of a diluent introduced into the solution.
- [c16] The method according to claim 11, wherein the absorption spectroscopy measurement is a UV/visible light spectroscopy measurement.
- [c17] The method according to claim 11, further comprising transporting the sample

of the solution using a pump.

- [c18] A system for controlling the concentration of a component in a composition, comprising:
a source of a composition comprising a liquid portion, wherein the liquid portion comprises a component to be monitored;
an absorption spectroscopy measurement apparatus for measuring the concentration of the component in a sample of the composition; and
feedback control means for controlling the concentration of the component in the composition based on the absorption spectroscopy measurement.
- [c19] The system according to claim 18, wherein the absorption spectroscopy system comprises a plurality of measurement cells.
- [c20] The system according to claim 18, further comprising means for directing the sample to an appropriate measurement cell depending on the concentration of the component to be monitored in the sample.
- [c21] The system according to claim 18, wherein the component to be monitored is a corrosion inhibitor.
- [c22] The system according to claim 21, wherein the corrosion inhibitor is benzotriazole, tolyltriazole, imidazole, triazole, benzothiazole, mercaptobenzotriazole, hydroquinone, gallic acid, pyragallol, catechol, recorsinol, or a combination thereof.
- [c23] The system according to claim 18, wherein the absorption spectroscopy measurement system is a UV/visible light spectroscopy measurement system.
- [c24] The system according to claim 18, further comprising a pump disposed between the source of the composition and the absorption spectroscopy measurement apparatus.
- [c25] A semiconductor processing system, comprising:
a chemical bath tank containing a solution for treating a semiconductor substrate;
one or more conduits for introducing process materials into the chemical bath,

the process materials comprising a component to be monitored;
an absorption spectroscopy measurement apparatus for measuring the
concentration of the component in a sample of the solution; and
feedback control means for controlling the concentration of the component in
the solution based on the absorption spectroscopy measurement.

[c26] The system of claim 25, wherein the absorption spectroscopy system comprises
a plurality of measurement cells.

[c27] The system of claim 25, further comprising means for directing the sample to
an appropriate measurement cell depending on the concentration of the
component to be monitored in the sample.

[c28] The system according to claim 25, wherein the component to be monitored is a
corrosion inhibitor.

[c29] The system according to claim 28, wherein the corrosion inhibitor is
benzotriazole, tolyltriazole, imidazole, triazole, benzothiazole,
mercaptobenzotriazole, hydroquinone, gallic acid, pyragallol, catechol,
recorsinol, or a combination thereof.

[c30] The system according to claim 25, wherein the absorption spectroscopy
measurement system is a UV/visible light spectroscopy measurement system.

[c31] The system according to claim 25, further comprising a pump disposed
between the chemical bath tank and the absorption spectroscopy measurement
apparatus.